

Atty Docket No.: 2000-0484B/N1085-90119

IN THE UNITED STATES PATENT AND TRADEMARK OFFICEIn Re Patent Application of:
Cheng et al.

Group Art Unit: 1765

Application No.: 10/649,472

Examiner: Chen, Kin Chan

Filing Date: August 27, 2003

For: Novel Chemical-Mechanical Polishing : Date: January 9, 2006
CMP Process for Shallow Trench Isolation :
..... :Mail Stop AP
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450RECEIVED
CENTRAL FAX CENTER
JAN 09 2006*Do not enter***AMENDMENT AFTER FINAL***fcc 1/9/06*

Sir:

This paper is responsive to the Office Action dated September 13, 2005. A petition for a one (1) month extension of time to extend the response due date to January 13, 2006 is included herewith. Kindly enter the following amendments:

Amendments to the Specification begin on page 2 of this paper.

Amendments to the Claims are reflected in the listing of claims which begins on page 3 of this paper.

Remarks begin on page 6 of this paper.

*entered per RCE
filed 2/9/06*